

第12回 関西コロキアム電子デバイスワークショップ

**参加費
無料**
(事前登録不要)

**2011年度IEEE主要ジャーナル・国際会議から
関西発の注目論文を選びすぐり、著者自らに
解説していただきます**



日 時 : 2012年10月26日(金) 10:10~17:45
 会 場 : 大阪大学中之島センター7F 講義室702
 (〒530-0005 大阪市北区中之島4-3-53)
 U R L : <http://www.ieee-jp.org/section/kansai/chapter/eds/>
 公用語 : 日本語



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講演プログラム 2012年10月26日(金) 10:10–17:45

I. CMOSナノデバイス・プロセス・回路

[10:15–11:30]

1. An accurate prediction model of temperature dependent current mismatch in all inversion and influence of subthreshold hump on mismatch characteristics [SSDM2011]
K. Sakakibara (Renesas Electronics)
2. Electric-field-induced band gap of bilayer graphene in ionic liquid [SSDM2011]
Y. Yamashiro (Osaka Univ.)
3. High-mobility Ge-on-insulator p-channel MOSFETs fabricated by lateral liquid-phase epitaxy [SISC2011]
Y. Suzuki (Osaka Univ.)

II. モデリング・信頼性

[13:00–14:15]

1. High reliable strain measurement for power devices using STEM-CBED method [IRPS2011]
N. Nakanishi (Renesas Electronics)
2. Impact of oxidation induced atomic disorder in narrow Si nanowires on transistor performance [Symp. VLSI Tech. 2011]
T. Zushi (Waseda Univ.)
3. Theory of resonant tunneling through a donor state [SSDM2011]
N. Mori (Osaka Univ.)

III. パワー・化合物・量子効果デバイス

[14:25–16:05]

1. CO₂ conversion with light and water by GaN photo-electrode [SSDM2011] S. Yotsuhashi (Panasonic)
2. GaN-based multi-junction diode with low reverse leakage current using p-type barrier controlling layer [IEDM2011] D. Shibata (Panasonic)
3. High performance SiC trench devices with ultra-low Ron [IEDM2011] T. Nakamura (ROHM)
4. Novel SiC power MOSFET with integrated unipolar internal inverse MOS-channel diode [IEDM2011] M. Uchida (Panasonic)

IV. ディスプレイ・センサ・新規デバイス

[16:15–17:30]

1. Acceleration sensor based on CMOS inverter having force balanced movable gate electrode [SSDM2011] M. Suzuki (Kansai Univ.)
2. Channel shortening phenomenon due to redox reaction in a lateral direction on In-Ga-Zn-O thin film transistors [AM-FPD2011] H. Kitakado (Sharp)
3. Mobility improvement in top-gate benzothienobenzothiophene organic transistors processed by spin coating [SSDM2011] F. Mochizuki (Osaka Pref. Univ.)